

No titl available.

Patent Number: DE4003623
Publication date: 1991-08-08
Inventor(s): OPPEL WERNER DR (DE)
Applicant(s):: KLOECKNER IONON (DE)
Requested Patent: DE4003623
Application Number: DE19904003623 19900207
Priority Number(s): DE19904003623 19900207
IPC Classification: C23C8/36
EC Classification: H01J37/32D1C1, H01J37/32F
Equivalents: CA2075299, EP0514391, WO9112628

Abstract

The invention relates to a process for controlling an installation for plasma treatment of workpieces. The installation has a constant voltage source for producing a glow discharge voltage V, which includes a control unit for controlling the magnitude of the glow discharge voltage V and a switch unit which can periodically switch off the glow discharge voltage V in various pulse-pause ratios. The installation also has a sensor for measuring the temperature of the workpiece, which is connected to the control unit so that the glow discharge voltage V is increased if the measured temperature is less than a given treatment temperature and decreased if the measured temperature is greater than the treatment temperature. The glow discharge voltage V is monitored so that if it falls below a lower threshold value the pulse-pause ratio of the glow discharge voltage V is reduced and if it exceeds an upper threshold value the pulse-pause ratio is increased.

Data supplied from the esp@cenet database - I2